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**Inventor Information**

Inventor One Given Name:: Masaru  
Family Name:: MITSUI  
Name Suffix::  
City of Residence:: Tokyo  
State or Prov. of Residence::  
Country of Residence:: JAPAN  
Inventor Two Given Name:: Haruhiko  
Family Name:: YAMAGATA  
Name Suffix::  
City of Residence:: Tokyo  
State or Prov. of Residence::  
Country of Residence:: JAPAN  
Inventor Three Given Name:: Masao  
Family Name:: USHIDA  
Name Suffix::  
City of Residence:: Tokyo  
State or Prov. of Residence::  
Country of Residence:: JAPAN  
Inventor Four Given Name::  
Family Name::  
Name Suffix::  
City of Residence::  
State or Prov. of Residence::  
Country of Residence::  
Inventor Five Given Name ::  
Family Name::  
Name Suffix::  
City of Residence::  
State or Prov. of Residence::  
Country of Residence::

**Correspondence Information**

Name Line One:: Oliff & Berridge PLC  
Address Line One:: P.O. Box 19928  
City:: Alexandria  
State or Province:: VA  
Postal or Zip Code:: 22320  
Telephone:: (703) 836-6400  
Fax:: (703) 836-2787  
Electronic Mail:: commcenter@oliff.com

**Application Information**

Title Line One:: PHOTOMASK BLANK, PHOTOMASK, METHODS OF  
Title Line Two:: MANUFACTURING THE SAME AND METHOD OF  
Title Line Three:: FORMING MICROPATTERN  
Title Line Four::

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**Continuity Information**

>This application is a:: National Stage of  
Application One:: PCT/JP99/04124  
Filing Date:: July 30, 1999  
Patent Number::  
which is a::  
>>Application Two::  
Filing Date::  
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**Prior Foreign Applications**

Foreign Application One:: 10-217433  
Filing Date:: July 31, 1998  
Country:: JAPAN  
Priority Claimed:: YES  
Foreign Application Two::  
Filing Date::  
Country::  
Priority Claimed::  
Foreign Application Three::  
Filing Date::  
Country::  
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